

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	9338	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:39
L2	28275	(mask or photomask or reticle or \$3PSM) near4 (set or trim\$4)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:46
L3	24236	\$3PSM or (mask or photomask or reticle) near4 (phase or shift \$3)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:47
L4	8300	(mask or photomask or reticle) same (semitransparen\$3 or semi transparen\$3 or attenuate or attenuating or attenuated or semitransluscen\$3 or semitransmi\$5 or partial\$3 near2 (transparen\$3 or transmi\$5)) or attPSM	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:48
L5	4517	(mask or photomask or reticle or \$3PSM) same (dummy or subresolution or sub resolution or (below or smaller than or less than) near3 (resolution or resolve or resolved or resolving)) same (structure or feature or pattern or grid or grating or array or opening or hole)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:49
L6	126	1 and 2 and 3 and 4 and 5	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:51

L7	73	6 and ((alternated or alternating or Levenson or Shibuya) near2 (phas\$3 or shift \$3) near2 (mask or photomask or reticle) or altPSM or alt PSM or (alternated or alternating or Levenson or Shibuya) near2 PSM)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:52
L8	53	6 not 7	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:52
L9	51	2 and 3 and 4 and 5 and ((alternated or alternating or Levenson or Shibuya) near2 (phas\$3 or shift \$3) near2 (mask or photomask or reticle) or altPSM or alt PSM or (alternated or alternating or Levenson or Shibuya) near2 PSM) not 7 not 8	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:53
L10	124	1 and 2 and 5 not 7 not 8 not 9	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:55
L11	117	1 and 3 and 4 and 5 not 7 not 8 not 9 not 10	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:56
L12	524	(mask or photomask or reticle or \$3PSM) same (set or trim\$4) same (dummy or subresolution or sub resolution or (below or smaller than or less than) near3 (resolution or resolve or resolved or resolving)) same (structure or feature or pattern or grid or grating or array or opening or hole)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:57

L13	37	1 and 12 not 7 not 8 not 9 not 10 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:58
L14	74	1 and 2 same 4 not 7 not 8 not 9 not 10 not 11 not 13	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 13:59
L15	4556	(improv\$3 or increas\$3 or maxim\$5) same ("depth of focus" or "DOF" or focus depth) or (improv\$3 or decreas\$3 or minim\$5) same (defocus)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 14:22
L16	5	1 and 2 and 5 same 15	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 14:23
L17	13	1 and 5 same 15 not 16	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 14:24
L18	30	5 same 15 not 16 not 17	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 14:25
L19	13504	(Infineon Technologies AG).as.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 15:00
L20	31	19 and (Dettmann-Wolfgang or Thiele-Jorg or Pforr-Rainer or Hennig-Mario or Zeiler-Karsten).in. not 7 not 8 not 9 not 10 not 11 not 13 not 14 not 16 not 17 not 18	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 15:04
L21	1	(19 or (Dettmann-Wolfgang or Thiele-Jorg or Pforr-Rainer or Hennig-Mario or Zeiler-Karsten).in.) and 2 and 15 not 7 not 8 not 9 not 10 not 11 not 13 not 14 not 16 not 17 not 18 not 20	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 15:13

L22	15249	((mask or photomask or reticle or \$3PSM) and (set or trim\$4)). clm.	US- PGPUB; USPAT	ADJ	ON	2008/02/18 15:54
L23	1284	((mask or photomask or reticle or \$3PSM) and ((dummy or subresolution or sub resolution) or (below or smaller than or less than) near3 (resolution or resolve or resolved or resolving)) and (dimension or width or size or structure or feature or pattern or grid or grating or array or opening or hole)). clm.	US- PGPUB; USPAT	ADJ	ON	2008/02/18 16:05
L24	668	(((alternated or alternating or Levenson or Shibuya) and (phas\$3 or shift \$3) and (mask or photomask or reticle)) or altPSM or alt PSM or ((alternated or alternating or Levenson or Shibuya) and PSM)).clm.	US- PGPUB; USPAT	ADJ	ON	2008/02/18 16:17
L25	303	(((improv\$3 or increas \$3 or maxim\$5) and ("depth of focus" or "DOF" or focus depth)) or ((improv\$3 or decreas\$3 or minim\$5) and defocus)).clm.	US- PGPUB; USPAT	ADJ	ON	2008/02/18 16:18
L26	0	22 and 23 and 24 and 25	US- PGPUB; USPAT	ADJ	ON	2008/02/18 16:20
L37	1634	430/394.ccls.	US- PGPUB; USPAT	ADJ	ON	2008/02/18 17:29
L38	490	1 and 37	US- PGPUB; USPAT	ADJ	ON	2008/02/18 17:29

L39	19477	(mask or photomask or reticle or \$3PSM) near2 (set or trim\$4)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 17:30
L40	103	38 and 39 not 7 not 8 not 9 not 10 not 11 not 13 not 14 not 16 not 17 not 18 not 20 not 21	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/02/18 17:39

2/ 18/ 08 5:56:55 PM

C:\ Documents and Settings\jruggles\ My Documents\ EAST\ Workspaces\ 10791763 + 10792693 (Sets of Masks to improve or maximize DOF).wsp